

Docket No. 197802US2S

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Wakako MORIYAMA, et al.

FILING DATE: Herewith

FOR: METHOD FOR MANUFACTURING SEMICONDUCTOR DEVICES USING THERMAL NITRIDE FILMS
AS GATE INSULATING FILMS

LIST OF INVENTORS' NAMES AND ADDRESSES

ASSISTANT COMMISSIONER FOR PATENTS
WASHINGTON, D.C. 20231

SIR:


Listed below are the names and addresses of the inventors for the above-identified patent application.

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A declaration containing all the necessary information will be submitted at a later date.

Respectfully Submitted,

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